

67,200-1230  
2003-0486

#### Abstract of the Disclosure

[0044] A temperature-sensing wafer position detection system and method which uses temperature to determine whether a wafer is properly positioned on a bake plate prior to commencement of a photolithography baking process, for example. The system includes a bake plate and a temperature-sensing apparatus which engages the bake plate and measures the change in temperature ( $\Delta T$ ) of the bake plate over a specified time interval to determine whether the wafer is properly or improperly positioned on the support. In the event that the  $\Delta T$  of the bake plate is at least as great as a given temperature change threshold value over a specified time interval, this indicates that the wafer is properly positioned for processing.